

An introduction to the newest Park Systems' nanoscale microscopy solutions. Empowering innovation across nanotechnology applications.

Atomic Force Microscopy (AFM) stands as a versatile and high-resolution tool for the characterization of advanced nanomaterials, offering powerful capabilities that extend far beyond topographical imaging. Its strength lies in the ability to perform correlative measurements of multiple physical properties—such as electrical conductivity, surface potential, nanomechanical stiffness, and even local chemical composition—all at the nanoscale.

In this presentation, we introduce the new FX Atomic Force Microscopy (AFM) series, which boasts a high level of built-in automation features that set it apart from other research AFMs on the market. Automation reduces the amount of manual handling of the equipment, thereby facilitating its use. It also dramatically reduces set-up time and eliminates user error and equipment breakage. An overview on the different key features and advantages of these series and different models will be presented.

We demonstrate this series to be the easiest, most versatile and cutting-edge platform for investigating a range of features on a nanometer scale such as 2D materials, low-dimensional optoelectronics, biopolymers, nanoparticles and nanofabricated devices.

During this symposium we prove Park Systems AFMs to be an indispensable, multi-functional platform for comprehensive nanoscale characterization across disciplines.